

### **PATENT**

#### IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: DANA SCRANTON ET AL.

**APPLICATION NO.:** 

10/055,467

FILED:

**JANUARY 22, 2002** 

FOR: VAPOR CLEANING AND LIQUID RINSING

PROCESS VESSEL

EXAMINER:

FRANKIE L. STINSON

ART UNIT:

1746

CONF. NO:

6380

# DECLARATION UNDER 37 CFR RULE 1.131 BY INVENTOR DANA SCRANTON

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

- I, Dana Scranton, declare as follows:
- I am an inventor of the invention described in U.S. Patent Application
   Serial No. 10/055,467 for a single vessel vapor cleaning and rinsing system.
- 2. I conceived of the invention described in the claims of Application Serial No. 10/055,467 before 08/31/1999. Attached as Exhibit A is Invention Disclosure No. D98-0067, which I prepared before 08/31/1999.

## Certificate of Mailing

I hereby certify that this paper (along with any referred to as being attached or enclosed) is being deposited with the United States Postal Service on the date shown below with sufficient postage in an envelope addressed to Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

Date of Deposit

Debbie Gilbert

- 3. After I prepared the Invention Disclosure attached as Exhibit A, I continued developing further ideas for the single vessel process tool described in the Invention Disclosure, both before and after 08/31/1999.
- 4. Upon information and belief, the invention described in Exhibit A was subsequently approved for patenting and provided to Patent Counsel in October 2000, for preparation of a patent application. Subsequently, I had several communications with Patent Counsel in connection with preparing a draft patent application, and subsequently a final patent application, which was filed 01/22/2002.
- 5. I declare that all statements made above of my own knowledge are true, and that all statements made above upon information and belief are believed to be true, and further, I acknowledge that willful false statements and the like are punishable by fine or imprisonment, or both, and may jeopardize the validity of the application or any patent issuing thereon.

Dated: 9-27-2005

Dana Scranton



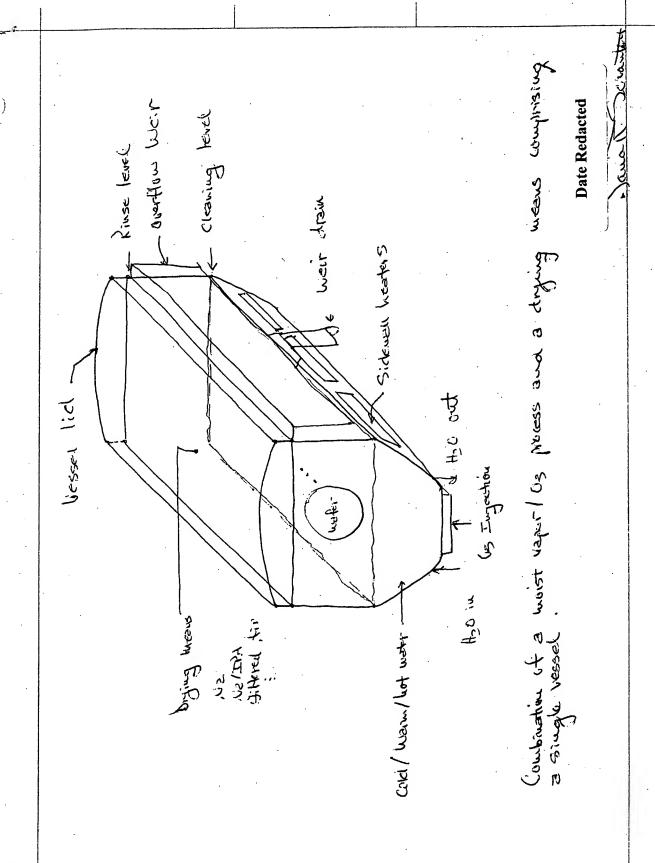
# **INVENTION DISCLOSURE**

SEMITOOL, INC.

D98-0067

IN CASE OF MULTIPLE INVENTORS: GET PAGE 2 OF THIS DISCLOSURE; EACH INVENTOR MUST FILL OUT INVENTOR INFORMATION.

LAOT III DE LA COLLINS DE LA C		
Note: 1. Use Ink or Type Only	and data	
2. Do not erase errors. Line through any errors, initial	and date. Le written explanation.: Drawings m	ay be below or attached.
3. Describe invention with drawings, sketches, etc. and a written explanation. Drawings may be below or attached.  If attached, the inventor(s) and witnesses must sign and date each sheet.		
4. Describe the advantages of this invention compared	to the current approach, if any.	
5 Inventor(s) and two (2) witnesses must sign and dat	e each sheet.	
6. Send original signed documents to the Intellectual Pr	roperty Department. Retain a pers	onal copy.
Inventor's Full Name (include middle initial, jr., sr., l,	II, etc.)	
Dana R. Scranton		
Check Box if there is more than one inventor (u	se page two of disclosure for	additional inventors)
Inventor's Physical Home Address:314 Hilltop Ave., K	alienell MT 59901	
Inventor's Physical Home Address:314 Hillop Ave., N	anspen, mi cocci	
•		
Inventor's Citizenship: US	•	
Title of Invention: Single vessel processor having in	combination a moist vapor-oz	one means and a drying
means		
Tool or Process: Organic Cleaning in Single Vessel	Division: Other	If Other, describe:
Surface Preparation		
Invention:		
Chatch Evaluation and Adventages: A single vessel pro	ocess tool incorporates a moist	vapor ozone process in which
sees is hubbled through water water being at a tempera	ture which tacilitiates vapor for	nation in the gas-phase region
sertained within a vessel which is above the surface of th	e water and which contains a se	MICONOLICION WATER OF DIGITALITY
of semiconductor wafers. Also incorporated within the sai	me vessel is a drying means, sa	ild drying means consisting of
but not limited to surface tension gradient drying, IPA dryi	ing, or dry gas drying.	
The principle advantage of this system is that is provides	for an omanic contaminant clea	mina process, rinsina process,
and drying process within a single vessel, thus facilitating	a smaller footprint for the equir	oment.
and drying process within a single vesser, thus rushing		
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		Delta of Films
Signature(s) of Inventor(s): \ and \ Detaut Date:	Date of Conception:	Date of First
Sketch/Drawing:		
Oloto, B. C.	The state of the s	·
	Date Redacted	



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